

## PATENT ABSTRACTS OF JAPAN

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(71)Applicant : SUMITOMO CHEM CO LTD

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(72)Inventor : TAGUCHI SATOSHI  
MURAKAMI SHINICHI

## (54) PRODUCTION OF HYDROGEN PEROXIDE SOLUTION OF HIGH PURITY

## (57)Abstract:

PURPOSE: To obtain a hydrogen peroxide solution of high purity which is optimal for a semiconductor producing process and in which metals, chloride ions and sulfurate radicals have been reduced by bringing crude hydrogen peroxide solution into contact with a specified ion exchange resin.

CONSTITUTION: A crude hydrogen peroxide solution of 20-30wt.% industrially produced by an anthraquinone method and having purity higher than the industrial one so called that used for electronic industry, etc., is brought into contact with an anion exchange resin and/or a cation exchange resin in multiple stages, and is brought into contact with a cation exchange resin of  $\leq 5$  degree of cross-linking in a final stage. The cation exchange resin is used as a hydrogen type. That is, after a column is filled with the cation exchange resin and mineral acid is passed through the resin to turn in into the hydrogen type, it is washed with water to remove excess mineral acid, the washed resin is used. The anion exchange resin is fed as a chlorine type or a hydroxyl type. That is, a column is filled with the and resin ammonium carbonate or ammonium bicarbonate is passed through the resin, and the resin thus obtained is used. Crude hydrogen peroxide solution is passed through the column filled with the anion and/or cation exchange resin to collect impurities.

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